

ISC150

ION SPUTTER COATER

The ISC150 Ion Sputter Coater uses a high-performance rotary vane pump to quickly generate a vacuum pressure below 3Pa, typically achieved with a pumping time of less than 3 minutes. Utilization of magnetron sputtering technology significantly reduces the thermal impact and bombardment damage of plasma on samples. It is particularly suitable for sputtering gold, platinum, and other noble metal layers on samples for Field Emission Scanning Electron Microscopy (FE-SEM).

Touchscreen automatic control, plug and play.

Magnetron sputtering
Finer Granularity

Rotary-tilting Stage
Uniform Coating

Large Chamber
Constant Pressure Control

SuPro Instruments LTD

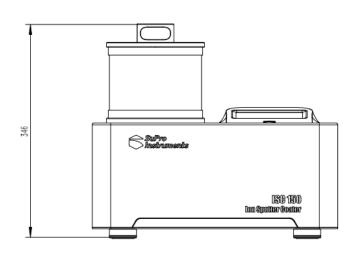
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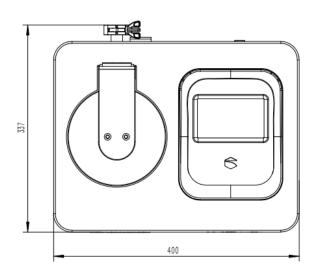
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Technical Specifications	Parameters
Vacuum Pump	Rotary Vane Pump
Pumping Speed	$\geqslant 4m^3/h$
Ultimate Vacuum	<1Pa
Working Pressure	4-10Pa (Constant Pressure Control)
Pumping Time	<3-5Min
Vacuum Gauge	Pirani Vacuum Gauge
Chamber	Ø150*120mm Scratch-resistant Quartz Glass
Sputtering Target	Ø50*0.1-1mm
Sputtering Power	Constant Power Magnetron Sputtering DC Power Supply (Max.20W, Max.100 mA, 0-800V DC)
Operation Mode	Touchscreen Control with the Control System Providing Interlock Protection Functions
Weight	~20kg
Dimension	400mm*337mm*346mm
Power Supply	100-220V AC, 50/60Hz Grounded Three-prong Plug
Power Consumption	<500W
Warranty	One Year
Remarks	The technical specifications and parameters listed above will be updated without prior notice. If you have any questions, please contact us.







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